ME 517: Micro- and Nanoscale Processes

Lecture 3: Scaling

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Scaling Laws

Scaling laws for force (WSN Trimmer, Sensors and Actuators, 19, 267, 1989).

F =

 $a = F/m = [s^F] [s^{-3}] =$

 $t = (2x/a)^{1/2} = (2xm/F)^{1/2} = ([s^1] [s^3] [s^-F])^{1/2} =$

$$\begin{bmatrix} s^{0.5} \\ s^2 \\ s^{3.5} \\ s^5 \end{bmatrix} \begin{bmatrix} s^{-2.5} \\ s^{-1} \\ s^{0.5} \\ s^2 \end{bmatrix}$$

 S^{I}

*s*²

 $\frac{s^3}{s^4}$

 S^{-2}

s⁻¹

 s^0

 S^{I}

 $s^{1.5}$

s^{0.5}

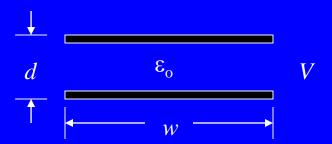
 S^{I}

 s^0

 $P = Fx/t = [s^{F}] [s^{1}]([s^{1}] [s^{3}] [s^{-F}])^{1/2} =$ $P/V = [s^{F}] [s^{1}]([s^{1}] [s^{3}] [s^{-F}])^{1/2} [s^{-3}] =$

Electrostatic Forces

Parallel plate capacitor of *w*-width *d*-distance between plates *V*- voltage



 $U = \frac{1}{2} CV^{2}$ $C = \varepsilon_{0} \frac{w^{2}}{d} \qquad V = Ed$ $U = \frac{1}{2} \varepsilon_{0} w^{2} dE^{2}$ $F = -\frac{dU}{dx} = -\frac{1}{2} \varepsilon_{0} \frac{d}{dx} [w^{2} dE^{2}]$ Continuum dielectric behavior $E = s^{0} \qquad F = s^{2}$ Continuum breakdown $E = s^{-0.5} \qquad F = s^{1}$

Micro/Nanoscale Physical Processes

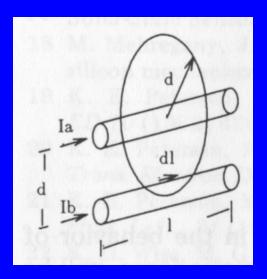
Magnetic Forces

Two wires carrying current

$$dF_b = I_b dl_b x B a$$

$$\nabla x B - c^{-2} \frac{\partial E}{\partial t} = \mu_o J$$

$$B_a = \frac{\mu_o i_a}{2\pi d}$$
$$F_b = i_b l B_a = \frac{\mu_o l i_b i_a}{2\pi d}$$



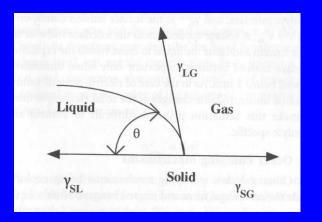
Constant current density J (Trimmer case C)

$$i = \int J dA = JA \qquad i = [s^0] [s^2]$$
$$F_b = [s^4]$$

Micro/Nanoscale Physical Processes

Surface Tension

Surface tension (γ) is the increase in energy as the surface area is increases.

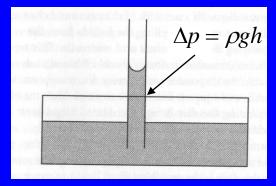


$$\Delta p = \frac{2(\gamma_{SG} - \gamma_{SL})}{r} = \frac{2\gamma_L \cos\theta}{r}$$

 $\gamma_{water} = 72.8 \text{ mN/m}$ r = 10⁻⁶ m $\Delta p \sim 100 \text{ kPa or 1 atm}$

Young's Equation

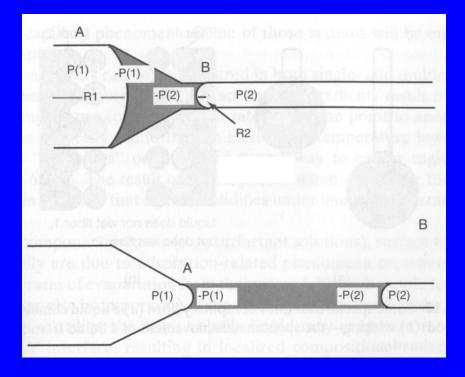
$$\gamma_{SL} + \gamma_{LG} \cos\theta = \gamma_{SG}$$



Micro/Nanoscale Physical Processes

Surface Tension

Capillary tube wetting



$$\Delta p = 2\gamma \cos\theta \left(\frac{1}{R_1} - \frac{1}{R_2}\right)$$

 $\theta < 90$ and $R_1 > R_2$ then $\Delta p < 0$

 $\theta < 90$ and $R_1 < R_2$ then $\Delta p > 0$

 $F_b = [s]$

Outline of Microfabrication Section

- •Introduction to Microfabrication
- •Lithography
- •Dry Etching Techniques
- •Additive Techniques
- •Bulk Micromachining
- •Surface Micromachining
- •Novel, quick, advanced techniques

Project 1:

- •Choose some topic of interest to you in the 'small' world
- •Can work in small groups of 1-4 people
- •Write a one paragraph abstract describing the topic and the scope of what you will write about.
 - •Due next Fri, Jan 24

Supplementary References

MEMS Handbooks

- •M. Madou, *Fundamentals of Microfabrication*, CRC Press 2000. ISBN 0-8493-9451-1
- M. Gad-el-Hak, *The MEMS Handbook*, CRC Press, 2002. ISBN 0-8493-0077-0.
- G.T.A. Kovacs, *Micromachined Transducers Sourcebook*, McGraw-Hill Co, 1998. ISBN 0-07-290722-3.

Electrical Engineering and Solid-State Physics texts

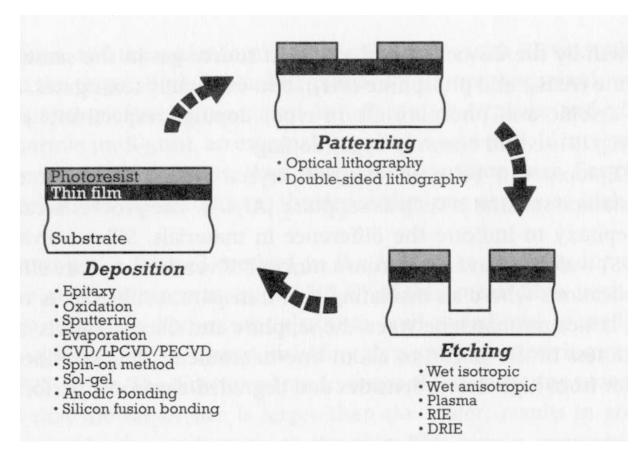
•S. A. Campbell, *The Science and Engineering of Microelectronic Fabrication*, Oxford University Press, 2001. ISBN 0-19-513606-5.

- N.W. Ashcroft, N.D. Mermin, *Solid State Physics*, B. Saunders Co, 1976. ISBN 0-03-083993-9.
- C. Kittel, *Introduction to Solid State Physics*, J. Wiley & Sons, 1986. ISBN 0-471-87474-4.

Outline of Introduction to Microfabrication and Lithography

- Basic Microfabrication Processes
- MEMS Materials
 - Silicon: Chemistry and Materials Properties
 - Metals
- Solid State Properties
 - Piezoresistivity
 - Piezoelectricity
- Photolithography
 - Photoresists
 - Resolution
 - Other Forms of Lithography

Basic Processes in Microfabrication



An Introduction to Microelectromechanical Systems Engineering, N. Maluf, Artech House, 2000.